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APPLICATION NO.	FI	ILING DATE	FIRST NAMED INVENTOR YASUNORI UETANI	ATTORNEY DOCKET NO.	CONFIRMATION NO. 8929	
09/323,230	(06/01/1999		2185-0343P		
2292	7590	06/25/2002				
		KOLASCH & BI	EXAMINER			
PO BOX 74 FALLS CH		A 22040-0747	CHU, JOHN S Y			
				ART UNIT	PAPER NUMBER	
				1752	22	
				DATE MAILED: 06/25/2002		

Please find below and/or attached an Office communication concerning this application or proceeding.

			**************************************		AS-22
7		Applica	tion No.	Applicant(s)	
		09/323,	230	TAKATA ET AL.	
	Office Action Summary		r	Art Unit	
a.		John S.		1752	
Period fo	The MAILING DATE of this commun	nication appears on t	he cover sheet wit	h the correspondence addi	'ess
A SH THE - Exte after - If the - If NC - Failu - Any	ORTENED STATUTORY PERIOD F MAILING DATE OF THIS COMMUN nsions of time may be available under the provisions SIX (6) MONTHS from the mailing date of this come period for reply specified above is less than thirty (3) period for reply is specified above, the maximum so tree to reply within the set or extended period for reply reply received by the Office later than three months and patent term adjustment. See 37 CFR 1.704(b).	IICATION. s of 37 CFR 1.136(a). In no e munication. 30) days, a reply within the st tatutory period will apply and y will, by statute, cause the a	event, however, may a re atutory minimum of thirty will expire SIX (6) MONT pplication to become AB/	ply be timely filed (30) days will be considered timely. HS from the mailing date of this com	munication.
1)	Responsive to communication(s) fi	iled on <i>14 June 200</i> 2	•		
2a)□	This action is FINAL .	2b)⊠ This action i	_	•	
3)□	Since this application is in conditio	·—		ers prosecution as to the	merits is
,—	closed in accordance with the praction of Claims	ctice under <i>Ex parte</i>	Quayle, 1935 C.D	0. 11, 453 O.G. 213.	
4) 🖂	Claim(s) 1 and 6-9 is/are pending in	n the application.			
	4a) Of the above claim(s) is/a	are withdrawn from c	onsideration.		
5)	Claim(s) is/are allowed.				
6)⊠	Claim(s) 1 and 6-9 is/are rejected.				
7)	Claim(s) is/are objected to.		¥ . *		
8)	Claim(s) are subject to restrict	ction and/or election	requirement.		
Applicat	ion Papers				
9) 🗌 '	The specification is objected to by th	e Examiner.			
10) 🔲	The drawing(s) filed on is/are:	a) accepted or b)	objected to by th	e Examiner.	
	Applicant may not request that any ob	-	•	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	
11) 🔲	The proposed drawing correction file			sapproved by the Examiner.	
	If approved, corrected drawings are re		Office action.	<i>y</i>	
12) 🔲	The oath or declaration is objected to	by the Examiner.			
Priority ι	ınder 35 U.S.C. §§ 119 and 120				
13)⊠	Acknowledgment is made of a claim	n for foreign priority u	ınder 35 U.S.C. §	119(a)-(d) or (f).	
a)	☑ All b) ☐ Some * c) ☐ None of:				
	1. ☐ Certified copies of the priority	documents have be	en received.		
	2. Certified copies of the priority	documents have be	en received in Ap	plication No	
* 0	3. Copies of the certified copies application from the Interresee the attached detailed Office action	national Bureau (PC	Γ Rule 17.2(a)).		age
	acknowledgment is made of a claim f		· ·		!:\
a) 🗌 The translation of the foreign lar	nguage provisional a	pplication has be	en received.	ррисацоп).
	Acknowledgment is made of a claim t	for domestic priority	under 35 U.S.C. {	§§ 120 and/or 121.	
Attachment	• •		√ 1_4		
2) Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (F nation Disclosure Statement(s) (PTO-1449) P	PTO-948) laper No(s)	4) Interview Si 5) Notice of In 6) Other:	ummary (PTO-413) Paper No(s). formal Patent Application (PTO-	52)
0.00					

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DETAILED ACTION

This Office action is in response to the RCE filed June 14, 2002.

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1, and 6-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over TACHIKAWA et al in view of a AOAI et al.

The claimed invention is drawn to an article comprising a substrate comprising a silicon wafer and a positive resist composition comprising a novolac resin; an o-quinonediazide sulfonic acid ester of a compound having a phenolic hydroxyl group; and a thioxanthone compound represented by the following formula (I):

TACHIKAWA ET AL discloses a photosensitive composition comprising a quinonediazide compound and a sensitizer wherein the sensitizers are disclosed in column 3, lines 3-15. Applicants are directed to line 12 for the suggestion of thioxanthone as an additive aromatic ketone.

TACHIKAWA ET AL lacks an explicit example using the claimed and disclosed thioxanthone, however it would have been *prima facie* obvious to one of ordinary skill in the art

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of photosensitive quinonediazide containing compositions to use any of the listed aromatic ketones with the reasonable expectation of same or similar results as disclosed in TACHIKAWA ET AL for the formation of positive and negative images. TACHIKAWA ET AL further lacks the explicit use of a silicon wafer as a substrate to coat the photosensitive composition.

TACHIKAWA ET AL, fails to explicitly disclose the presence of a sensitizer as claimed such as thioxanthone, however the use of sensitizers is to expand the spectral range and the activate the acid generators are well known and can easily be added to provide known and expected results.

AOAI ET AL '143 discloses in the FIELD OF THE INVENTION (col. 1,lines 26-32) that photosensitive compositions can be used as photoresist compositions or lithographic printing plates wherein the application of the photosensitive composition would decide the substrate to be coated, such that a silicon wafer and a printing plate substrate are analogous based on the desired application. Clearly the photosensitive composition comprising a quinonediazide compound, a phenolic resin and a thioxanthone is known in the art and merely coating the composition on a silicon wafer or a printing plate substrate is obvious to the skilled artisan depending on the desired application.

It would have been *prima facie* obvious to one of ordinary skill in the art of photosensitive composition to first coat the photosensitive compositions of TACHIKAWA et al on a silicon wafer as demonstrated taught by the FIELD OF INVENTION disclosed in AOAI ET AL. It would also been *prima facie* obvious to the skilled artisan to add thioxanthone in place of 1,2-benzanthraquinone of Example to function as a sensitizer to expand the spectral sensitivity of

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the compositions as well as help activate the acid generators and reasonably expect same or

similar results as recited in TACHIKAWA ET AL.

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (703) 308-2298. The

examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for this Group is (703) 305-5433.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (703) 308-0661.

John S. Chu

Primary Examiner, Group 1700

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J.Chu June 23, 2002